# ABSTRACT

## PATTERNING SUBSTRATES EMPLOYING MULTIPLE CHUCKS

The present Invention is directed towards a method for patterning first and second substrates in a nanoimprlnt lithography system, the method including, inter alia, concurrently positioning the first and second substrate on a first and second substrate chuck; positioning a nanoimprint material on the first and second substrate; removing the first substrate from the first substrate chuck while concurrently obtaining a spatial relationship between the first substrate and a nanoimprint mold assembly and imprinting a pattern in the nanoimprint material on the first substrate with the nanoimprint mold assembly; and separating the nanoimprint mold assembly from the nanoimprint material on the first and second substrate, with the first and second substrates being subjected to substantially the same process conditions.

Fig 1